

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	74414	(photomask near substrate and printed near pattern and pre near etch near dimensions and etch near recipe and post near etch dimensions).clm.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/04/02 10:01
L2	0	(photomask near substrate and printed near pattern and pre near etch near dimensions and etch near recipe and post near etch near dimensions).clm.	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/04/02 10:01